

Application No.: 09/783,598
Amendment Under 37 C.F.R. §1.116 dated March 23, 2005
Reply to the Office Action dated December 23, 2004

REMARKS

Claims 1 – 16 remain pending in the present application. Claims 7 – 16 were withdrawn from consideration. The rejections set forth in the Office Action are respectfully traversed below. Entry of this Amendment and an early Notice of Allowance are respectfully requested.

The Prior Art Rejections

Claims 1 – 3 and 5 were rejected under 35 U.S.C. §102 over **Beilin et al.** (USP 6,733,685). Claims 4 and 6 were rejected under 35 U.S.C. §103 over **Beilin**, in view of **Onishi et al.** (USP 5,459,368). It is submitted that nothing in the prior art teaches or suggests all of the features recited in the present claimed invention.

For instance, amended independent claim 1 recites “posts being anisotropically etched silicon.” The cited prior art does not teach at least this feature. **Beilin** is directed to a surface planarization technique by CMP (Chemical Mechanical Polishing) that comprises forming interlayer connection conductors (VIAs) by a plating method, applying and then curing an insulative material, and planarizing the surface by CMP. The alleged corresponding “posts” of **Beilin** are formed by covering conductive posts by applying an insulating resin. Such posts (formed by plating) in **Beilin** are not silicon nor anisotropically etched silicon.

In contrast, the present invention relates to a “front-and-back” electrically conductive substrate that includes silicon posts formed by anisotropically etching a silicon wafer substrate. According to the present invention, a front-and-back electrically conductive substrate having the claimed structural characteristic of posts being anisotropically etched silicon (of the silicon wafer substrate) achieves a fine pitch for the posts to form a high aspect ratio. Nothing in the primary

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reference to **Beilin** teaches or suggests the claimed posts. Nothing in the further reference to **Onishi** remedies the deficiencies in the primary reference to **Beilin**. For at least these reasons, the present claimed invention patentably distinguishes over the prior art. Accordingly, entry of this Amendment is respectfully requested to place the present application into condition for allowance.

If, for any reason, it is felt that this application is not now in condition for allowance, or if the Examiner wishes additional explanations of the present invention, the Examiner is requested to contact Applicant's undersigned attorney at the telephone number indicated below to arrange for an interview to expedite the disposition of this case.

In the event that any fees are due in connection with the filing of this paper, please charge any fees to Deposit Account No. 50-2866.

Respectfully submitted,

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